

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2415	(118/723e.ccls. or 118/723er.ccls. or 156/345.43-345.47.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S2	2620	141/285-286.ccls. or 141/37.ccls. or 141/44-47.ccls. or 141/54.ccls. or 141/301-302.ccls. or 141/367.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S3	8169	137/262-264.ccls. or 137/454.2 or 137/560.ccls. or 137/561r.ccls. or 137/561a.ccls. or 137/571-576.ccls. or 137/590.ccls. or 137/594-596.ccls. or 137/599.01.ccls. or 137/599.05-599.07.ccls. or 137/602.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S4	498	261/127.ccls. or 261/131.ccls. or 261/146-147.ccls. or 261/150.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S5	11236	118/715.ccls. or 118/728.ccls. or 118/50.ccls. or 156/345.29.ccls. or 156/345.33.ccls. or 156/345.34.ccls. or 156/345.35.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.51.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S6	7368	261/64.1.ccls. or 261/65.ccls. or 261/75-76.ccls. or 261/94-96.ccls. or 261/100-102.ccls. or 261/105.ccls. or 261/108-109.ccls. or 261/113.ccls. or 261/114.1.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39

S7	31866	(118/715.ccls. or 118/728.ccls. or 118/50.ccls. or 156/345.29.ccls. or 156/345.33.ccls. or 156/345.34.ccls. or 156/345.35.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.51.ccls.) or (137/262-264.ccls. or 137/454.2 or 137/560.ccls. or 137/561r.ccls. or 137/561a.ccls. or 137/571-576.ccls. or 137/590.ccls. or 137/594-596.ccls. or 137/599.01.ccls. or 137/599.05-599.07.ccls. or 137/602.ccls.) or (141/285-286.ccls. or 141/37.ccls. or 141/44-47.ccls. or 141/54.ccls. or 141/301-302.ccls. or 141/367.ccls.) or (261/127.ccls. or 261/131.ccls. or 261/146-147.ccls. or 261/150.ccls.) or (261/19-22.ccls. or 261/23.1.ccls. or 261/40.ccls. or 261/42.ccls. or 261/62-63.ccls.) or (261/64.1.ccls. or 261/65.ccls. or 261/75-76.ccls. or 261/94-96.ccls. or 261/100-102.ccls. or 261/105.ccls. or 261/108-109.ccls. or 261/113.ccls. or 261/114.1.ccls.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S8	33629	S1 or S7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39
S9	2655	261/19-22.ccls. or 261/23.1.ccls. or 261/40.ccls. or 261/42.ccls. or 261/62-63.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/31 06:39

S10	1	10/549285	US-PGPUB; USPAT	OR	ON	2008/02/05 10:50
S11	2	((("6429456") or ("6566174"))).PN.	US-PGPUB; USPAT	OR	OFF	2008/02/05 11:47
S12	51681	(oxygen or "o.sub.2") adj2 (plasma or radical or ion)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:07
S13	12378	(nitrogen or "n.sub.2") adj2 (plasma or radical or ion)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:07
S14	3733	S12 and S13	US-PGPUB; USPAT	OR	ON	2008/02/05 12:07
S15	3358	S14 and (substrate or wafer or article or semiconductor)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:08
S16	7962	(oxygen or "o.sub.2") adj2 (plasma or radical or ion) with (source or generat\$3)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:09
S17	2211	(nitrogen or "n.sub.2") adj2 (plasma or radical or ion) with (source or generat\$3)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:10
S18	458	S16 and S17	US-PGPUB; USPAT	OR	ON	2008/02/05 12:10
S19	429	S18 and (substrate or wafer or article or semiconductor)	US-PGPUB; USPAT	OR	ON	2008/02/05 12:10
S20	5	Yamazaki near Kazuyoshi.in.	US-PGPUB; USPAT	OR	ON	2008/02/05 14:20
S21	30	Aoyama near Shintaro. in.	US-PGPUB; USPAT	OR	ON	2008/02/05 14:21
S22	19	Igeta near Masanobu. in.	US-PGPUB; USPAT	OR	ON	2008/02/05 14:21
S23	66	Shinriki near Hiroshi. in.	US-PGPUB; USPAT	OR	ON	2008/02/05 14:21
S24	84	S20 S21 S22 S23	US-PGPUB; USPAT	OR	ON	2008/02/05 14:21
S25	16044	(rotat\$3 near4 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) and uniform\$3	US-PGPUB; USPAT	OR	ON	2008/02/05 15:52

S26	955	S25 and plasma and (semiconductor adj (process\$3 or product \$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2008/02/05 15:53
S27	4380	(rotat\$3 near4 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) and (uniform\$3 with (advantag\$3 or benefit or achiev\$3 or obtain \$3))	US-PGPUB; USPAT	OR	ON	2008/02/05 15:55
S28	298	S27 and plasma and (semiconductor adj (process\$3 or product \$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2008/02/05 15:55
S29	1	("6,093,252").PN.	US-PGPUB; USPAT	OR	OFF	2008/02/05 16:08

2/ 5/ 2008 5:32:26 PM

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